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(54) Title: CHARGE ALTERATION USING ULTRAVIOLET RADIATION

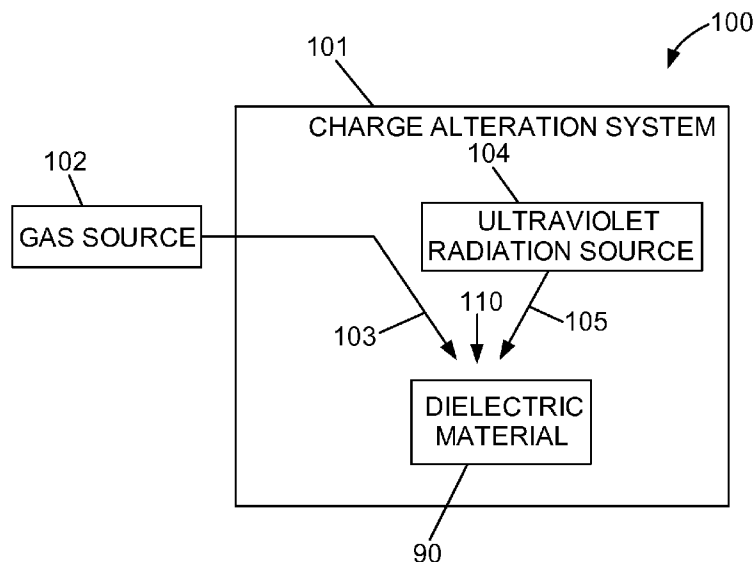


Fig. 1

(57) Abstract: A system(109) for altering charge of a dielectric material (90) uses ultraviolet radiation. The system includes a gas source (102) and an ultraviolet radiation source (104). The gas source (102) introduced a gas (103) to a region adjacent the dielectric material (90). The ultraviolet radiation source (104) is arranged to irradiate the region to adjust charge on the dielectric material. A method of altering charge on a dielectric material (90) is also disclosed in which a gas (103) is introduced to a region adjacent the dielectric materia (90)1. The region is then irradiated with the ultraviolet radiation (105) to alter charge on the dielectric material (90).



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CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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